

AlN Uniformity data for Cambridge ALD tool

- AlN plasma recipes (TMA and N₂/H₂ plasma)

- 300°C growth rate=0.65Å/cycle
- Chuck position thickness and uniformity
- 1. Left 18.94 nm (2.34% Δ wrt center)
- 2. Top 18.44 nm (-0.37% Δ wrt center)
- 3. Right 18.51 nm (-0.03% Δ wrt center)
- 4. Bottom 18.23 nm (-1.51% Δ wrt center)
- 5. Center 18.53

- 400°C growth rate=0.69Å/cycle
- Chuck position thickness and uniformity
- 1. Left 15.21 nm (2.91% Δ wrt center)
- 2. Top 14.61 nm (-1.15% Δ wrt center)
- 3. Right 14.89 nm (0.74% Δ wrt center)
- 4. Bottom 14.54 nm (1.63% Δ wrt center)
- 5. Center 14.78

